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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

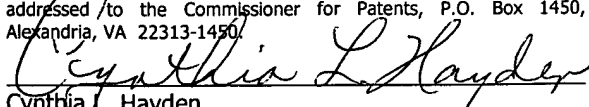
Applicant:	Justin K. Brask et al.	§	Art Unit:	2811
Serial No.:	10/626,336	§	Examiner:	Ori Nadav
Filed:	July 24, 2003	§	Atty Docket:	ITL.1022US P16709
For:	Forming a High Dielectric Constant Film Using Metallic Precursor	§	Assignee:	Intel Corporation

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REPLY TO FINAL REJECTION

Sir:

In response to the final rejection mailed March 30, 2005, reconsideration is requested in view of the following remarks.

Date of Deposit: April 18, 2005
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Cynthia L. Hayden